



SHEET 1 OF 1

INFORMATION DISCLOSURE
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APPLICATION

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Doug van den BROEKE, et al.FILING DATE
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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<i>CME</i>		EP 1 202 119 A1	05-02-2002	ASML Masktools B.V.		<input checked="" type="checkbox"/> <input type="checkbox"/>
<i>CME</i>		WO 03/054626 A1	07-03-2003	ADVANCED MICRO DEVICES, INC.		<input checked="" type="checkbox"/> <input type="checkbox"/>

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
<i>CME</i>		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," Optical Microlithography XIII, Proceedings of SPIE, 2000, pp 1156-1162, Vol. 4000
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C. Luerhast

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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